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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/427,675	10/27/1999	ERIC JACQUINOT	JACQUINOT=7	3607

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EXAMINER

DEO, DUY VU

ART UNIT PAPER NUMBER

1765

DATE MAILED: 04/10/2002

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Please find below and/or attached an Office communication concerning this application or proceeding.

Office Action Summary	Application No.	Applicant(s)
	09/427,675	JACQUINOT ET AL.
	Examiner	Art Unit
	DuyVu n Deo	1765

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --

Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133).
- Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

1) Responsive to communication(s) filed on 18 March 2002.

2a) This action is **FINAL**. 2b) This action is non-final.

3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

4) Claim(s) 17-36 is/are pending in the application.

4a) Of the above claim(s) _____ is/are withdrawn from consideration.

5) Claim(s) _____ is/are allowed.

6) Claim(s) 17-36 is/are rejected.

7) Claim(s) _____ is/are objected to.

8) Claim(s) _____ are subject to restriction and/or election requirement.

Application Papers

9) The specification is objected to by the Examiner.

10) The drawing(s) filed on _____ is/are: a) accepted or b) objected to by the Examiner.

Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).

11) The proposed drawing correction filed on _____ is: a) approved b) disapproved by the Examiner.

If approved, corrected drawings are required in reply to this Office action.

12) The oath or declaration is objected to by the Examiner.

Priority under 35 U.S.C. §§ 119 and 120

13) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).

a) All b) Some * c) None of:

1. Certified copies of the priority documents have been received.
2. Certified copies of the priority documents have been received in Application No. _____.
3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

* See the attached detailed Office action for a list of the certified copies not received.

14) Acknowledgment is made of a claim for domestic priority under 35 U.S.C. § 119(e) (to a provisional application).

a) The translation of the foreign language provisional application has been received.

15) Acknowledgment is made of a claim for domestic priority under 35 U.S.C. §§ 120 and/or 121.

Attachment(s)

1) Notice of References Cited (PTO-892) 4) Interview Summary (PTO-413) Paper No(s). _____
2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 5) Notice of Informal Patent Application (PTO-152)
3) Information Disclosure Statement(s) (PTO-1449) Paper No(s) _____ 6) Other: _____

DETAILED ACTION

1. The disclosure is objected to because of the following informalities: the summary is missing in the specification.

Appropriate correction is required.

Claim Rejections - 35 USC § 103

2. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negated by the manner in which the invention was made.
3. Claims 17-36 are rejected under 35 U.S.C. 103(a) as being unpatentable over Jacquinot et al. (US 6,043,159) and Hosali et al. (US 5,738,800).

Jacquinot teaches a polishing an integrated circuit in which isolation layer, including silicon oxide and silicon nitride, is polished by an abrasive composition which comprises an aqueous acid suspension of individualized colloidal silica particles not linked to each other by siloxane bonds. The pH of the composition is about 1.5-4, the abrasives have diameters about 10-50 nm and a concentration of about 15-30% (col. 2, line 39-65; col. 4, line 1-10). Unlike claimed invention he doesn't describe that the support is impregnated with an abrasive liquid composition. However, since the polishing pad is soaked with the abrasive liquid composition during the polishing, the abrasive liquid composition would get into the abrasive pad and

therefore, this would create claimed polishing pad that impregnated with an abrasive composition.

Unlike claimed invention, Jacquinot doesn't describe having a surfactant in the abrasive composition. Hosali teaches a method of polishing the oxide layer using a surfactant in the abrasive composition. The surfactant can be anionic or nonionic (summery, table 1-3). It would have been obvious for one skill in the art at the time of the invention in light of Hosali to add a surfactant because Hosali teaches that a surfactant is used to affect the polishing rate of the silicon nitride in the oxide/nitride composite surface. As shown in tables 1-3, the surfactant would increase the polishing selectivity of oxide over the nitride.

Tables 1-3 of Hosali show a variety of polishing parameters including the surfactant % is from 0-5. Therefore, it would have been obvious for one skill in the art that the processing parameters is determined through test runs in order to achieve the optimum polishing parameters to polishing the oxide with an anticipation of an expected result.

4. Any inquiry concerning this communication or earlier communications from the examiner should be directed to DuyVu n Deo whose telephone number is 703-305-0515.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is 703-308-0661.

DVD
April 5, 2002

ROBERT KUNEMUND
PRIMARY EXAMINER